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RESEARCH PAPER

Effect of various plant growth regulators on yield and quality of guava (*Psidium guajava* L.) cv. LUCKNOW-49

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Abstract : The present investigation was carried out to determine the suitable and optimum concentration of boron and plant growth regulators for maximum productivity and quality of guava cv. LUCKNOW-49 during *Kharif* season. From the present study it can be concluded that the treatment $T_{10}(0.2\% \text{ boron} + \text{GA}_3 60 \text{ ppm} + \text{NAA} 150 \text{ ppm} + \text{ethrel 750 ppm})$ was found best for physical parameters and treatment $T_5(0.2\% \text{ boron} + \text{NAA} 150 \text{ ppm} + \text{othrel 750 ppm})$ was found best for physical parameters and treatment $T_5(0.2\% \text{ boron} + \text{NAA} 150 \text{ ppm})$ for yield point of view, while for quality point of view the treatment $T_9(0.2\% \text{ boron} + \text{ethrel 1000 ppm})$ was found best. As far as the relative economics of the treatment is concerned, the maximum net realization of Rs. 1,72,807 per hectare with highest 1:6.6 cost benefit ratio (CBR) was obtained by the treatment $T_5(0.2\% \text{ boron} + \text{NAA} 150 \text{ ppm})$ as compared to other treatments. Therefore, the treatment $T_5(0.2\% \text{ boron} + \text{NAA} 150 \text{ ppm})$ is best among all treatment for higher production.

Key Words : Guava (Psidium guajava L.), Boron, NAA, Ethrel yield, Quality

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